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ANDREW DOYLE; United States of America**Assignee:** MICRION CORP. United States of America
[News, Profiles, Stocks and More about this company](#)**Published / Filed:** 2000-07-26 / 1998-04-15**Application Number:** CN1998000806122**IPC Code:** Advanced: [G03F 1/00](#); [H01J 37/305](#); [H01L 21/027](#); [H01L 21/3213](#); [H01L 21/768](#);
Core: [H01L 21/70](#); [more...](#)
IPC-7: [H01J 37/305](#); [H01L 21/306](#); [H01L 21/3213](#); [H01L 21/465](#);**ECLA Code:** [G03F1/00Z](#); [H01J37/305B2](#); [H01L21/027](#); [H01L21/3213B](#); [H01L21/768C8L](#);**Priority Number:** 1997-04-16 [US1997000834356](#)**INPADOC Legal Status:** None **Get Now:** [Family Legal Status Report](#)**High Resolution****Family:**

PDF	Publication	Pub. Date	Filed	Title
	WO9847172A1	1998-10-22	1998-04-15	PATTERN FILM REPAIR USING A GAS ASSISTED FOCUSED PARTICLE BEAM SYSTEM
	US6042738	2000-03-28	1997-04-16	Pattern film repair using a focused particle beam system
<input checked="" type="checkbox"/>	JP2001521678T2	2001-11-06	1998-04-15	
	EP1641034A2	2006-03-29	1998-04-15	Pattern film repair using a gas assisted focused particle beam system
	EP0976152B1	2007-08-08	1998-04-15	PATTERN FILM REPAIR USING A GAS ASSISTED FOCUSED PARTICLE BEAM SYSTEM
	EP0976152A1	2000-02-02	1998-04-15	PATTERN FILM REPAIR USING A GAS ASSISTED FOCUSED PARTICLE BEAM SYSTEM
<input checked="" type="checkbox"/>	DE69838211T2	2008-06-19	1998-04-15	REPARATUR VON MIKROSTRUKTUREN DURCH GASUNTERSTÜTZTES ÄTZEN MIT FOKUSSierten IONENSTRAHLEN
	DE69838211C0	2007-09-20	1998-04-15	REPARATUR VON MIKROSTRUKTUREN DURCH GASUNTERSTÜTZTES ÄTZEN MIT FOKUSSierten IONENSTRAHLEN
<input checked="" type="checkbox"/>	CN1261458T	2000-07-26	1998-04-15	Pattern film repair using a gas assisted focused

				particle beam system
<input checked="" type="checkbox"/>	CN1261458A	2000-07-26	1998-04-15	Pattern film repair using a gas assisted focused particle beam system
<input checked="" type="checkbox"/>	CN1199246C	2005-04-27	1998-04-15	Pattern film repair using a gas assisted focused particle beam system
<input checked="" type="checkbox"/>	CA2286638AA	1998-10-22	1998-04-15	PATTERN FILM REPAIR USING A GAS ASSISTED FOCUSED PARTICLE BEAM SYSTEM
<input checked="" type="checkbox"/>	AU6975098A1	1998-11-11	1998-04-15	Pattern film repair using a gas assisted focused particle beam system
<input checked="" type="checkbox"/>	AT0369622E	2007-08-15	1998-04-15	REPARATUR VON MIKROSTRUKTUREN DURCH GASUNTERSTÜTZTES ÄTZEN MIT FOKUSSierten IONENSTRAHLEN
14 family members shown above				

Forward
References:

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PDF	Patent	Pub.Date	Inventor	Assignee	Title
	US7264905	2007-09-04	Nagamura; Yoshikazu	Renesas Technology Corp.	Photomask, and method and apparatus for producing the same

Other Abstract
Info:

None



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